



PLANAR CARBON NANOTUBE NETWORKS: HIGHLY CONDUCTIVE, FLEXIBLE & TRANSPARENT ELECTRODES, FIELD EMITTERS & INFRA-RED SENSORS

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Sep. 2010





1) Motivation

2) Flexible, transparent CNT film conductors

Electro-Optical Characterisation

Mechanical Durability

2) CNT Planar Field Emitters

3) Fully Suspended CNT IR Sensor





BUT WHY DO THIS?



One of many problems...





We want...

- flexibility
- transparency

We need...

- high current densities

IN THE FUTURE

- bottom-up fabrication



LG.PHILIPS LCD



A) FLEXIBLE, TRANSPARENT CNT FILM CONDUCTORS



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Electro-Optical Characterisation

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Electro-Optical Characterisation



 Simply tuneable optical and electrical characteristics







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Mechanical Durability

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OUTLINE

1) Motivation

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B) FIELD EMISSION & WHY CNTs?



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$$\mathbf{J} = \mathbf{A} \left(\beta^2 \mathbf{E}^2 / \phi \right) \exp \left(-B \phi^{3/2} / \beta E \right)$$



K. B. K. Teo, et al., APL 79 (2001) 1534



B) PLANAR CNT FIELD EMITTERS



M. Cole, C. Li, et. al. submitted



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B) PLANAR CNT FIELD EMITTERS



B) PLANAR CNT FIELD EMITTERS

 Consistently low turn on field (<1.5 V/µm) throughout

Thresh. field/Emission Current
1.15 V/μm / 2.88 mA (roll.)
1.30 V/μm / 1.48 mA (scr. prntd.)
1.40 V/μm / 1.38 mA (vac. filtd.)

✓ Enhancment, β (α aspect ratio)
66.2 (roll.)
29.0 (vac. Filtd.)
1.6 (scr. Prntd.)

✓ Low sheet resistance →
electrodeless field emitters

 Scrn. Printed: High impurity content in commercial CNT paste adds a ballast resistance

- Increases uniformity

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 BUT reduced current density / brightness

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CNT ALIGNMENT MCHANISMS



[1] M. Cole, M. Mann, et. al. *unpublished data* [2] M. Hersam, et. al. *Nat. Nanotech.*, **3** (2008), 387

[3] S. M. Huang, et al., Adv. Mat., 15 (2003), 19, 1651
[4] C. Kocabas, et al., Small, 1 (2005), 1110
[5] Z. Yuegang, et al., APL, 79 (2001), 19





C) FULLY SUSPENDED CNT IR SENSOR

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Fabrication



C) FULLY SUSPENDED CNT IR SENSOR



SUMMARY

- Binderless flexible CNT film transfer onto PC substrates
 - Highly scalable and inexpensive
 - Low sheet resistance 2.3 Ω/\square @ T_{550} = 10%
 - Potential for controlled transparency
 - Robust to intense mechanical treatment: flexing and strain
 - Strain >30%
- Flexible field emitters based on a variety of CNT films
 - Electrode-less fabrication
 - Low threshold fields (<1.5 V/ μ m) with high emission currents (mA)
 - Importance of balast resistance to improve uniformity
- Mechanically extruded CNTs
 - High material use efficiency
 - IR response demonstrated (Sensitivity ~ 1.35)
 - Bolometric





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- M. Mann
- C. Li
- P. Hiralal





- X. Xu

AIXTRON - K. B. K.Teo

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• Various EC consortia inc.

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- CANDICE, etc (EU FP6),
- EPSRC
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- Collaborators
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 - National Research Council-Institut Photonics and Nanotechnology,
 - York Probe Sources Ltd,
 - Xenocs SA,
 - Czech Technical University,
 - Chalmers University of Technology,
 - D'Appolonia S.p.A.,
 - Nokia,
 - Samsung





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THANK YOU FOR YOUR ATTENTION.

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EHT = 12.00 kV Date :1 Jun 20 WD = 7.0 mm Time :14:24:45

> PET subst Sheared H film (30 µm Cathode Celguard LiPF6 + P Sheared film (30 µm

> > TNT10 Sep. 2010





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